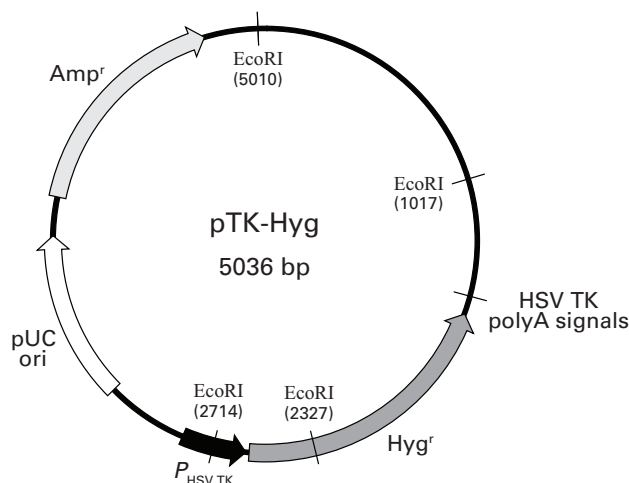


pTK-Hyg Vector Information

GenBank Accession No.: U40398

PT3082-5

Catalog No. 631750



pTK-Hyg.Vector Map

Description

pTK-Hyg is a selection vector that confers hygromycin resistance in mammalian cells for the selection of stably transformed cells. pTK-Hyg is especially useful for selection of double-stable cell lines using the Tet-On[®] or Tet-Off[®] Gene Expression Systems because the absence of an enhancer element on pTK-Hyg prevents the unwanted activation of pTRE- and pBI-derived plasmids upon cointegration into the host cell's genome.

Use

pTK-Hyg can be cotransfected into the host cell line with an expression plasmid that contains a gene of interest using any standard transfection technique. Most mammalian cell lines require 200 µg/ml of Hygromycin to select for stably transformed cells.

Location of Features

- HSVTK polyA signals: 1473–1478 & 1486–1491 (complementary)
- Hyg^r (hygromycin resistance gene): 1537–2574 (complementary)
- $P_{\text{HSV TK}}$ (HSVTK promoter): 2588–2835 (complementary)
- pUC origin of replication: 3152–3795
- Amp^r (ampicillin resistance gene; beta-lactamase): 3943–4803

Propagation in *E. coli*

- Suitable host strains: DH5 α [™] and other general purpose strains.
- Selectable marker: plasmid confers resistance to ampicillin (50 µg/ml) on *E. coli* hosts.
- *E. coli* replication origin: pUC

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